PVD Vacuum Coating Unit

Abstract

A vacuum coating unit includes a reactive gas inlet (12), at least one PVD coating source (8, 21) with a laminar cathode (11) and a substrate carrier (6) containing a multiplicity of substrates (7), wherein the substrate carrier (6) forms a twodimensional horizontal extent, and this carrier is positioned between at least two PVD coating sources, and that the multiplicity of substrates (7) are cutting tools with at least one cutting edge (E) in the peripheral margin region of the laminar substrate (7), which are deposed distributed in a plane of the twodimensional extent of the substrate carrier (6), wherein the substrate carrier (6) is disposed in a horizontal plane (3) in the vacuum process chamber (1) spaced apart between the laminar cathodes (11) of the at least two PVD coating sources (8, 21) and positioned such that at least a portion of each of the at least one cutting edge (E) includes an active cutting edge (E') and this active cutting edge is oriented opposite at least one of the cathodes (11) of the PVD coating sources (8, 21) exposed at any time in the line of sight.

Fig. 10a